## Highly fcc-textured Pt-Al alloy films grown on MgO(001) showing enhanced spin Hall efficiency IMR, Tohoku Univ.<sup>1</sup>, CSRN, Tohoku Univ.<sup>2</sup>, CSIS, Tohoku Univ.<sup>3</sup> °Yong-Chang Lau<sup>1,2</sup>, Takeshi Seki<sup>1,2</sup>, Koki Takanashi<sup>1,2,3</sup> E-mail: lau.yong.chang.d8@tohoku.ac.jp

Reducing the power consumption is of paramount importance for increasing the competitiveness of spintronic devices for next-generation computing. The power efficiency of a spin-orbit torque switching device is governed by the figure of merit  $\xi_{DL}\sigma_{SH}$  where  $\xi_{DL}$  and  $\sigma_{SH}$  are the damping-like spin Hall efficiency and the associated spin Hall conductivity of the material where charge-to-spin conversion via the spin Hall effect (SHE) occurs. When the intrinsic mechanism is the primary source of SHE, alloying is expected to boost up  $\xi_{DL}$  while maintaining  $\sigma_{SH}$ , thus the power efficiency can be enhanced. Substantial efforts have been devoted to explore the SHE in Pt-based alloys (by alloying Pt with Al[1], Hf[1], Au[2], Cu[3], MgO[4], etc.) because face-centered cubic (fcc) Pt is the elemental material featuring the highest  $\sigma_{SH}$ . Nevertheless, a general guideline for the choice of successful material combination has been lacking. Here, by revisiting the SHE in Pt<sub>100-x</sub>Al<sub>x</sub> alloys, we reveal the crucial role of highly-ordered fcc texture for efficient charge-to-spin conversion using Pt-based alloys.

We have grown 2 series of  $Pt_{100-x}Al_x(\sim 6nm)/CoFeB(2nm)/AlOx(3nm)$  heterostructures of varying Al concentration *x* by magnetron sputtering on MgO(001) and SiO<sub>2</sub> substrates. The growth of  $Pt_{100-x}Al_x$  layers on MgO was carried out at a substrate temperature of ~300°C whereas other layers on MgO and the entire stacks on SiO<sub>2</sub> were grown at ambient temperature. X-ray diffraction (XRD) spectra indicate that  $Pt_{100-x}Al_x$  alloy films on MgO are highly textured and subsequently crystallize in fcc Pt, fcc-based L1<sub>2</sub>-ordered Pt<sub>3</sub>Al and bcc-based B2-PtAl as *x* is varied from 0 to ~ 48. In contrast, the Pt (*x* = 0) film grown on SiO<sub>2</sub> is polycrystalline and shows a relatively weak fcc(111) XRD peak. The peak intensity diminishes monotonically with increasing *x* suggesting the disordered alloy films on SiO<sub>2</sub> gradually become amorphous. This is consistent with the limited solubility (~10%) of Al in Pt. The CoFeB layers are in-plane magnetized. We systematically compare the charge-to-spin conversion efficiency of these two series of structures using the in-plane harmonic Hall technique. We surprisingly found that  $\xi_{DL}$  and  $\sigma_{SH}$  of highly-textured  $Pt_{100-x}Al_x$  alloy films on MgO largely overwhelm those of poorly-textured  $Pt_{100-x}Al_x$  alloy films on SiO<sub>2</sub>. For  $Pt_{78}Al_{22}$  (*x* = 22), we obtained  $\xi_{DL} \sim 0.20$  for the MgO series and only  $\xi_{DL} \sim 0.06$  for the SiO<sub>2</sub> series which we attribute to the strong correlation between the  $Pt_{100-x}Al_x$  crystallinity and the SHE. We will also discuss other factors that will influence the SHE upon alloying.

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